

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1634	(phosphorus or phosphide or phos\$6 or p) and getter\$3 and (nickel or ni) and (tantalum or ta)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 14:19
L2	438	1 and (@ad<"19970610" or @rlad<"19970610")	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 14:20
L3	828	(phosphorus or phosphide or phos\$6 or p) and getter\$3 and (nickel or ni) and ((tantalum or ta) same gate)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 14:20
L4	73	3 and (@ad<"19970610" or @rlad<"19970610")	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 17:25
L5	1	((nickel adj phosphide) or (nickel adj phosphorus) or "nip.sub.2" or "ni.sub.2p") and (gate same (tantalum or ta)) and (@ad<"19970610" or @rlad<"19970610")	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 16:38
L6	2378	((nickel adj phosphide) or (nickel adj phosphorus) or "nip.sub.2" or "ni.sub.2p") and (@ad<"19970610" or @rlad<"19970610")	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 16:33
L7	51	((((nickel adj phosphide) or (nickel adj phosphorus) or "nip.sub.2" or "ni.sub.2p") same (source or drain)) and (@ad<"19970610" or @rlad<"19970610"))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 16:54
L8	8	"nip" and (gate same (tantalum or ta)) and (@ad<"19970610" or @rlad<"19970610")	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 16:38
L9	79	((((ni adj p) or "ni/p" or "ni.sub.xp" or "ni.sub.3p") same (source or drain)) and (@ad<"19970610" or @rlad<"19970610"))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 16:56
L10	76	9 not 7	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 17:23
L11	21195	(nickel or ni) with (phosphorus or p) with (silicon or si)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 17:24

L12	91	11 and (gate with (tantalum or ta))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 17:50
L13	13	12 and (@ad<"19970610" or @rlad<"19970610")	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 18:39
L14	24	"ni.sub.3p"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 17:50
L15	81	nip2 or nip3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 17:52
L16	2	15 and (gate with (tantalum or ta))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 17:52
L17	89999	ni2p or ni3p or nip	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 17:52
L18	27	17 and (gate with (tantalum or ta))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 17:52
L19	3	18 and (@ad<"19970610" or @rlad<"19970610")	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 17:52
L20	43	migration with nickel with temperature	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 18:39
S1	2	"6303415".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/02 14:18
S2	2052	tft and crystalliz\$5 and gate and source and drain	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/04 16:12
S3	704	(tft and crystalliz\$5 and gate and source and drain) and cataly\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/04 14:40

S4	576	((tft and crystalliz\$5 and gate and source and drain) and cataly\$3) and (active adj layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/04 14:41
S5	270	((((tft and crystalliz\$5 and gate and source and drain) and cataly\$3) and (active adj layer)) and getter\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/04 14:46
S6	212	(((((tft and crystalliz\$5 and gate and source and drain) and cataly\$3) and (active adj layer)) and getter\$3) and tantalum and nickel	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/04 14:48
S7	5	(((((tft and crystalliz\$5 and gate and source and drain) and cataly\$3) and (active adj layer)) and getter\$3) and tantalum and nickel) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/04 16:13
S8	303	(crystalliz\$5 same silicon same cataly\$3) and getter\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/04 16:13
S9	24	((crystalliz\$5 same silicon same cataly\$3) and getter\$3) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 11:32
S10	2	"5550070".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/04 17:10
S11	6	("5112764"   "5147826"   "5275851"   "5330935"   "5403772"   "5426064").PN.	USPAT	OR	ON	2002/12/04 17:45
S12	44	"5550070".URPN.	USPAT	OR	ON	2002/12/04 18:06
S13	168	phosphorus same nickel same getter\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 11:31
S14	19	(phosphorus same nickel same getter\$3) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 12:01
S15	2005	gate with tantalum	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 12:00
S16	840	(gate with tantalum) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 13:45

S17	31	((gate with tantalum) and @ad<"19970610") and crystalliz\$5 and cataly\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 13:35
S18	148	(nickel or ni) with (source or drain) with channel	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:48
S19	20	((nickel or ni) with (source or drain) with channel) with concentration	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 13:37
S20	74	((nickel or ni) with (source or drain) with channel) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:15
S21	149	cataly\$3 with channel with less	USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:21
S22	109	(cataly\$3 with channel with less) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:16
S23	47	((cataly\$3 with channel with less) and @ad<"19970610") and (nickel or ni)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:16
S24	0	(cataly\$3 with channel with less) and "5.times.10.sup.16."	USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:21
S25	3	(ni or nickel) with channel with "5.times.10.sup.16"	USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:23
S26	0	(ni or fe or co or pd or pt or cu or au) with channel with "5.times.10.sup.16"	USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:25
S27	3	(nickel or iron or gold or copper or platinum or palladium or cobalt) with channel with "5.times.10.sup.16"	USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:26
S28	0	(nickel or iron or gold or copper or platinum or palladium or cobalt) with channel with "5.times.10.sup.15"	USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:26
S29	0	(nickel or iron or gold or copper or platinum or palladium or cobalt) with channel with "5.times.10.sup.14"	USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:26

S30	1	(nickel or iron or gold or copper or platinum or palladium or cobalt) with channel with "5.times.10.sup. 17"	USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:26
S31	5	(nickel or iron or gold or copper or platinum or palladium or cobalt) with channel with "1.times.10.sup. 16"	USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:31
S32	0	(nickel or iron or gold or copper or platinum or palladium or cobalt) with channel with "1.times.10.sup. 15"	USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:45
S33	2	"6303415".pn.	USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:45
S34	77	(nickel or ni) same (source or drain) same channel same order\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:51
S35	16	((nickel or ni) same (source or drain) same channel same order\$1) same concentration	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 14:51
S36	2	"5550070".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2002/12/06 17:32
S37	370	(interlayer with insulat\$3 with silicon with nitride) and (interlayer with insulat\$3 with (acrylic or polyimide or polyamide or epoxy or epoxies)) and gate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/06/06 12:32
S38	37	((interlayer with insulat\$3 with silicon with nitride) and (interlayer with insulat\$3 with (acrylic or polyimide or polyamide or epoxy or epoxies)) and gate) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/06/06 12:33
S39	2	"5550070".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/09/30 20:08
S40	2258	silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 18:16
S41	968	(silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 18:42

S42	67	(silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) same source same drain same gate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 15:28
S43	17	((silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) same source same drain same gate) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 16:14
S44	6	("5112764"   "5147826"   "5275851"   "5330935"   "5403772"   "5426064").PN.	USPAT	OR	ON	2003/12/08 15:38
S45	54	"5550070".URPN.	USPAT	OR	ON	2003/12/08 16:13
S46	1	((silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) same source same drain same gate) and (concentration with nickel with (source or drain) with channel)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 16:16
S47	6	((silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) same source same drain same gate) and (concentration same nickel same (source or drain) same channel)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 16:32
S48	1	((silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) same source same drain same gate) and (concentration same (iron or palladium or copper) same (source or drain) same channel)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 18:17
S49	1	((silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) same source same drain same gate) and (concentration same iron same (source or drain) same channel)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 16:33
S50	6	(silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) and (concentration same (iron or palladium or copper) same (source or drain) same channel)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 17:00
S51	171	(silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) and (phosphorus with getter\$3 with nickel)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 17:00

S52	2	((silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) and (phosphorus with getter\$3 with nickel)) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 17:05
S53	19	((silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) and (phosphorus with getter\$3 with nickel)) and @ad<"19980610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 17:11
S54	96	(silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) and (nickel with source with drain with channel)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 17:12
S55	24	((silicon with (nickel or ni) with (crystallization or crystaliz\$3 or amorphous) ) and (nickel with source with drain with channel)) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 17:12
S56	14	("5147826"   "5275851"   "5481121"   "5492843"   "5501989"   "5529937"   "5534716"   "5543352"   "5550070"   "5580792"   "5585291"   "5612250"   "5643826"   "5654203").PN.	USPAT	OR	ON	2003/12/08 17:21
S57	1370	silicon with iron with (crystallization or crystaliz\$3 or amorphous)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 18:16
S58	3	(silicon with iron with (crystallization or crystaliz\$3 or amorphous) ) and (concentration same (iron or palladium or copper) same (source or drain) same channel)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 18:41
S59	6	(concentration with (nickel or iron or palladium or copper) with source with drain with channel) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 18:42
S60	30	concentration with (nickel or iron or palladium or copper) with source with drain with channel	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 20:13

S61	19	("5244819"   "5534716"   "5608232"   "5616506"   "5639698"   "5643826"   "5700333"   "5736438"   "5773309"   "5773329"   "5821138"   "5834071"   "5834345"   "5869363"   "5879977"   "5897347"   "5923962"   "5956579"   "6087245").PN.	USPAT	OR	ON	2003/12/08 18:48
S62	0	concentration with nickel with source with drain with channel with magnitude	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 20:16
S63	29	concentration with nickel with source with drain with channel	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 20:14
S64	0	nickel with source with drain with channel with magnitude	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 20:17
S65	4	nickel with source with drain with channel with (double or times)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 20:17
S66	2	nickel with source with drain with channel with higher	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 20:18
S67	6	nickel with source with drain with channel with lower	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 20:25
S68	165	nickel with channel with concentration	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 20:25
S69	34	(nickel with channel with concentration) and @ad<"19970610"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 20:26
S70	9019939	((nickel with channel with concentration) and @ad<"19970610") no (energy adj laboratory)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2003/12/08 20:26
S71	11872	(resistance or resistivity) with silicide	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/06/01 15:30



S72	1131	((resistance or resistivity) with silicide) with electric\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/06/01 15:31
S73	705978	electrical adj resistivity of silicide	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/06/01 15:31
S74	94	electrical adj resistivity with silicide	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/06/01 15:51
S75	4	(aluminum adj silicide) same tantalum same (resistivity or resistance)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/06/01 15:36
S76	11	(aluminum adj silicide) with (resistivity or resistance)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/06/01 15:39
S77	4600	tantalum with (resistivity or resistance)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/06/01 15:37
S78	260	(tantalum with (resistivity or resistance)) with electrical	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/06/01 15:37
S79	494	aluminum with silicide with (resistivity or resistance)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/06/01 15:39
S80	52	(aluminum with silicide with (resistivity or resistance)) with electric\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/06/01 15:39
S81	611	electrical adj resistivity with silicon	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/06/01 15:51
S82	41	electrical adj resistivity adj silicon	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2004/06/01 15:52